

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	2	"6642131".pn. (jp2003-008011-\$ jp2000-349287-\$ jp2003-124460-\$ jp2003-347297-\$ JP2003-179051-\$).did.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/02/27 16:24
S2	2	"US 20070096104"	US-PGPUB; USPAT; USOCR; DERWENT	AND	ON	2008/02/27 16:27
S3	183	((NOBUYUKI) near2 (IKARASHI)).INV. ((TORU) near2 (TATSUMI)).INV.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/02/27 16:30
S4	12055	silicon same hafnium same oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:35
S5	9737	"mis fet" or misfet	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:36
S6	355521	metal adj oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:36
S7	146	S4 S5 S6	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:36
S8	2760	(257/66 OR 257/213). CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:36

S9	2	S3 S7	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:36
S10	86316	(metal adj oxide) and gate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:41
S11	145	S4 S5 S10	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:41
S12	86316	(metal adj oxide) and gate and (nitride or oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:42
S13	145	S4 S5 S10 S12	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:42
S14	60	(halfnium with silicon with oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:43
S15	503	hfsio	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:43
S16	12	S4 S5 S10 S12 S15	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:43
S17	195009	silicon adj nitride	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:45

S18	4	polycrystalline S16	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/27 16:52
S19	195219	silicon adj nitride	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S20	12082	silicon same hafnium same oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S21	9742	"mis fet" or misfet	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S22	86447	(metal adj oxide) and gate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S23	86447	(metal adj oxide) and gate and (nitride or oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S24	504	hfsio	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S25	12	S20 S21 S22 S23 S24	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22
S26	4	polycrystalline S25	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:22

S27	63	hfsio "%"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:28
S28	128	hfsiox	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:44
S29	13	hfsiox "%"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:44
S30	2870	silicate with hafnium	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:47
S31	688	(silicate with hafnium) "%"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:48
S32	524	(silicate with hafnium) "% composition	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:48
S33	369	(silicate with hafnium) "% composition table	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:49
S34	35	S28 S30	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 10:53
S35	44	"Hf.sub.xSi.sub.1-xO. sub.2"	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 11:04

S36	3	(US-20030218223-\$ or US-20050070126-\$ or US-20030045080-\$). did.	US-PGPUB	AND	ON	2008/02/28 11:31
S37	1	polycrystalline S36	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 11:32
S38	605	(silicate with hafnium) polycrystalline	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/02/28 11:40
S39	95	(silicate with hafnium) polycrystalline	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	SAME	ON	2008/02/28 11:40
S40	72	(hafnium adj silicate) polycrystalline	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	SAME	ON	2008/02/28 11:41
S41	16	(hafnium adj silicate) polycrystalline	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	WITH	ON	2008/02/28 11:42
S42	4791	(257/66 OR 257/213 438/591 257/410 438/24).CCLS.	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/02/28 12:02
S43	13333	silicon same hafnium same oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S44	10059	"mis fet" or misfet	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18

S45	93021	(metal adj oxide) and gate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S46	93021	(metal adj oxide) and gate and (nitride or oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S47	156	S43 S44 S45 S46	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S48	63	(halfnium with silicon with oxide)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S49	13333	silicon same hafnium same oxide	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S50	150	hfsiox	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S51	3174	silicate with hafnium	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S52	0	S51 S48 S47 S49 S50	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:18
S53	14362	S51 S48 S47 S49 S50	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/08/27 15:18

S54	10122	misfet or mis?fet or (mis adj fet)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/08/27 15:19
S55	12530	(high adj k) or high?k	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/08/27 15:19
S56	5	S54 S55	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	ADJ	ON	2008/08/27 15:19
S57	288	(S51 S48 S47 S49 S50) and S54	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/08/27 15:20
S58	124	(S51 S48 S47 S49 S50) and S54 and S51	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2008/08/27 15:20
S59	5655	silicate with quaternary	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:33
S60	23	quaternary adj silicate	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:33
S61	11	(hf or hafnium) and S60	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:34
S62	18	(hf or hafnium) and (ternary adj silicate)	US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:35

S63	1	high "20030218223"	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:41
S64	1	high "20030218223". pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	AND	ON	2008/08/27 15:41

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